



IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicant : Ilya Perlov et al.

Art Unit : 3724

Serial No. : 09/507,172

Examiner : Timothy V. Eley

Filed : February 18, 2000

Title : CHEMICAL MECHANICAL POLISHING SYSTEM HAVING MULTIPLE POLISHING STATIONS AND PROVIDING RELATIVE LINEAR MOTION

Commissioner for Patents  
Washington, D.C. 20231

RESPONSE

In response to the action mailed May 9, 2002, please amend the application as follows:

In the claims:

Please amend the claims to read as follows:

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TECHNOLOGY CENTER R3700

1. (Amended Twice) A polishing apparatus, comprising:  
a rotatable support member rotatable about a first axis;  
at least two polishing surfaces arranged at respective angular positions about said first axis;

at least one substrate head assembly supported on said rotatable support member and capable of supporting thereon a substrate in contact with a selected one of said polishing surfaces and affording relative linear and reciprocal movement between said selected polishing surface and said substrate head assembly while said substrate supported on said substrate head assembly is engaged with said selected polishing surface;

wherein said at least one substrate head assembly is linearly and reciprocally movable in said rotatable support member.

CERTIFICATE OF MAILING BY FIRST CLASS MAIL

I hereby certify under 37CFR §1.8(a) that this correspondence is being deposited with the United States Postal Service as first class mail with sufficient postage on the date indicated below and is addressed to the Commissioner for Patents, Washington, D.C. 20231.

September 9, 2002

Date of Deposit

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Nikia M. Mc Nillion

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